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(71) Applicant (for all designated States except US): **ASML NETHERLANDS B.V.** [NL/NL]; De Run 6501, NL-5504 DR Veldhoven (NL).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **GLUSHKOV, Denis** [RU/DE]; Felsenweg 18, 58453 Witten (DE). **BANINE, Vadim** [NL/NL]; Nierslaan 2, NL-5704 NK Hel-mond (NL). **MOORS, Johannes, Hubertus, Josephina** [NL/NL]; Dierdonkiaan 56, NL-5709 MT Helmond (NL). **SJMAENOK, Leonid, Aizikovitch** [NL/NL]; Jos Francotteweg 6c, NL-6291 GP Vaals (NL). **SALASCHENKO, Nikolai Nikolaevich** [RU/RU]; Izhorskaya str. 11, apt. 1, Nizhny, 603024 (RU).(74) Agent: **SLENDERS, Peter**; ASML Netherlands B.V., De Run 6504, NL-5504 DR Veldhoven (NL).

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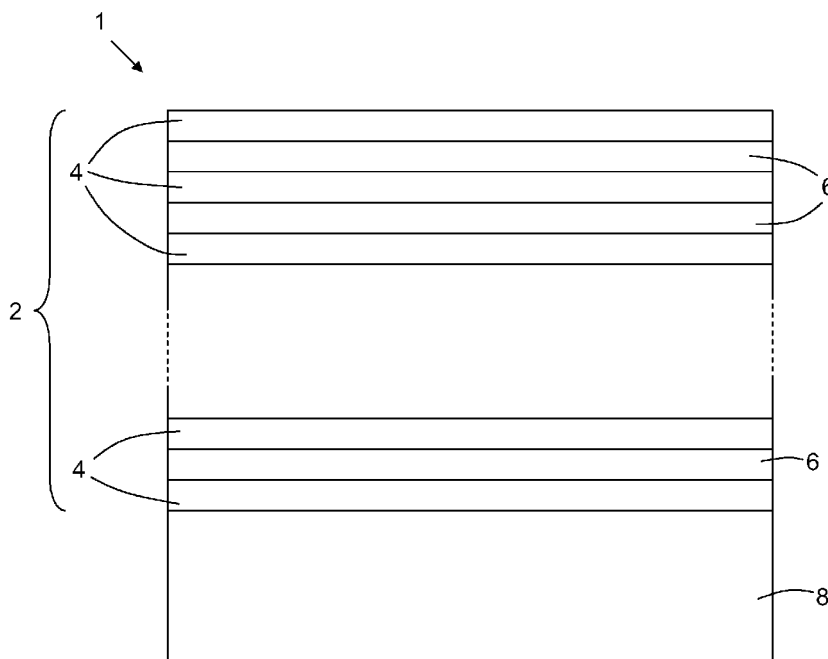


Figure 3

(57) Abstract: A multilayer mirror is constructed and arranged to reflect radiation having a wavelength in the range of 2-8 nm. The multilayer mirror has alternating layers selected from the group consisting of: Cr and Sc layers, Cr and C layers, C and B₄C layers, U and B₄C layers, Th and B₄C layers, C and B₉C layers, La and B₉C layers, U and B₉C layers, Th and B₉C layers, La and B layers, C and B layers, U and B layers, and Th and B layers.



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